

L Number	Hits	Search Text	DB	Time stamp
1	14	(barrier\$2) near7(wet adj2 etch\$4) and ((contact\$2 adj hole\$2 via adj hole\$2 through adj hole\$2) same((barrier\$2 liner\$2)with (titanium aluminum "tio.sub.2" "al.sub.2o.sub.3"))))	USPAT; US-PGPUB	2004/08/06 18:21
2	1878	((contact\$2 adj hole\$2 via adj hole\$2 through adj hole\$2) same((barrier\$2 liner\$2)with (titanium aluminum "tio.sub.2" "al.sub.2o.sub.3"))))	USPAT; US-PGPUB	2004/08/06 18:07
3	14	(barrier\$2) near7(wet adj2 etch\$4) and ( ((contact\$2 adj hole\$2 via adj hole\$2 through adj hole\$2) same((barrier\$2 liner\$2)with (titanium aluminum "tio.sub.2" "al.sub.2o.sub.3"))))	USPAT; US-PGPUB	2004/08/06 18:22
4	46	((contact\$2 adj hole\$2 via adj hole\$2 through adj hole\$2) same((barrier\$2 liner\$2)with (titanium aluminum "tio.sub.2" "al.sub.2o.sub.3"))and (atomic adj layer adj deposit\$4 ald)	USPAT; US-PGPUB	2004/08/06 18:22
5	68	((barrier\$2) near4 (bottom lower)) near7( etch\$4) and ((contact\$2 adj hole\$2 via adj hole\$2 through adj hole\$2) same((barrier\$2 liner\$2)with (titanium aluminum "tio.sub.2" "al.sub.2o.sub.3"))))	USPAT; US-PGPUB	2004/08/06 18:28
6	61	(plug\$2 fill\$4)and (((barrier\$2) near4 (bottom lower)) near7( etch\$4) and ((contact\$2 adj hole\$2 via adj hole\$2 through adj hole\$2) same((barrier\$2 liner\$2)with (titanium aluminum "tio.sub.2" "al.sub.2o.sub.3"))))	USPAT; US-PGPUB	2004/08/06 18:18
7	5	((plug\$2 fill\$4)and (((barrier\$2) near4 (bottom lower)) near7( etch\$4) and ((contact\$2 adj hole\$2 via adj hole\$2 through adj hole\$2) same((barrier\$2 liner\$2)with (titanium aluminum "tio.sub.2" "al.sub.2o.sub.3")))) and (atomic adj layer adj deposit\$4 ald)	USPAT; US-PGPUB	2004/08/06 18:21
8	91010	((manufactur\$4 fabricat\$4 method)near15(contact\$2))	EPO; JPO; DERWENT	2004/08/06 18:21
9	718	(atomic adj layer adj deposit\$4 ald)	EPO; JPO; DERWENT	2004/08/06 18:23
10	55	((contact\$2 adj hole\$2 via adj hole\$2 through adj hole\$2) same((barrier\$2 liner\$2)with (titanium aluminum "tio.sub.2" "al.sub.2o.sub.3"))and (atomic adj layer adj deposit\$4 ald)	USPAT; US-PGPUB	2004/08/06 18:22
11	9	( ((contact\$2 adj hole\$2 via adj hole\$2 through adj hole\$2) same((barrier\$2 liner\$2)with (titanium aluminum "tio.sub.2" "al.sub.2o.sub.3"))and (atomic adj layer adj deposit\$4 ald)) not ( ((contact\$2 adj hole\$2 via adj hole\$2 through adj hole\$2) same((barrier\$2 liner\$2)with (titanium aluminum "tio.sub.2" "al.sub.2o.sub.3"))and (atomic adj layer adj deposit\$4 ald))	USPAT; US-PGPUB	2004/08/06 18:22
12	993	(atomic adj layer adj deposit\$4 ald)	EPO; JPO; DERWENT	2004/08/06 18:24
13	29	((manufactur\$4 fabricat\$4 method)near15(contact\$2)) and ( (atomic adj layer adj deposit\$4 ald))	EPO; JPO; DERWENT	2004/08/06 18:25
14	0	(wet near3 etch\$4)and (((manufactur\$4 fabricat\$4 method)near15(contact\$2)) ) and ( (atomic adj layer adj deposit\$4 ald)))	EPO; JPO; DERWENT	2004/08/06 18:25
15	10	( etch\$4)and (((manufactur\$4 fabricat\$4 method)near15(contact\$2)) ) and ( (atomic adj layer adj deposit\$4 ald)))	EPO; JPO; DERWENT	2004/08/06 18:25
16	0	((barrier\$2) near4 (bottom lower)) near7( etch\$4) and ((contact\$2 adj hole\$2 via adj hole\$2 through adj hole\$2) same((barrier\$2 liner\$2)with (titanium aluminum "tio.sub.2" "al.sub.2o.sub.3"))and (((manufactur\$4 fabricat\$4 method)near15(contact\$2)) )	EPO; JPO; DERWENT	2004/08/06 18:28
17	3	((barrier\$2) near4 (bottom lower)) and( etch\$4) and ((contact\$2 adj hole\$2 via adj hole\$2 through adj hole\$2) and((barrier\$2 liner\$2)with (titanium aluminum "tio.sub.2" "al.sub.2o.sub.3"))and (((manufactur\$4 fabricat\$4 method)near15(contact\$2)) )	EPO; JPO; DERWENT	2004/08/06 18:29